

E-MRS Spring Meeting 2014 - Symposium H: ALTECH 2014 Analytical Techniques for Precise Characterization of Nano Materials

Metrology is a prerequisite for the development of novel materials on the nanoscale. It supports the correlation of material properties and functionalities. The expected contributions should demonstrate how analytical techniques enable a deep understanding of new materials. This symposium will be organized by major European National Metrology Institutes and Imec.

Hot topics

- 1. X-Ray diffraction, tomography, scattering and spectrometry based applications on advanced materials and in nanoscience
- 2. Recent developments of ion beam techniques for characterization of lateral and vertical thin films
- 3. New developments for optical spectroscopic measurements, large-area nanostructured highrefractive index materials measurement and modeling, optical scatterometry by coherent light
- 4. Techniques for thermal characterization of thin films
- 5. Methodologies for thin films, nanostructure, interfacial and nanostrain characterizations of semiconductor and advanced material systems
- 6. Scanning probe techniques for high resolution characterization of organic, hybrid and inorganic semiconductors
- 7. Analytical techniques for characterization of surface chemistry
- 8. Characterization of functionalized surfaces for e.g. biosensing and bioanalytics
- 9. Novel instrumentation for e.g. nanoanalysis, next generation of highest resolution microscopy including near-field methods, characterization of metallic and dielectric based superlenses
- 10. Ultra-trace analysis using complementary metrology
- 11. Reference and calibration samples for nanometrology

Invited speakers

- Wim Coene, ASML, The Netherlands
- Thierry Conard, IMEC, Belgium
- David Ginger, University of Washington, USA
- Séverine Gomes, CETHIL, France
- Jaime Gomez-Rivas, FOM, The Netherlands
- Poul-Erik Hansen, DFM, Denmark
- Ludger Koenders, PTB, Germany
- Jae Cheol Lee, Samsung Advanced Institute of Technology, South Korea
- Maria Luisa Polignano, ST Microelectronics, Italy
- Wolfgang Unger, BAM, Germany

EMRS 2014 Spring Meeting - Symposium H

Technical Sessions: May 26-30 2014 Venue: Congress Center Lille / France

Info: www.emrs-strasbourg.com

Organizers:

Burkhard Beckhoff, PTB, Germany
Fernando Araujo de Castro, NPL, U.K.
Omar El Gawhary, VSL, The Netherlands
Petr Klapetek, CMI, Czech Republic
Cor Claeys, Imec, Belgium